



# **SIMS Analysis of C and N Fluences in Genesis Samples**

---

**Yunbin Guan, Don Burnett, Ju-Young Kim**  
**(Caltech)**

**Amy Jurewicz**  
**(ASU)**



## Motivation of This Study

---

- **C and N lie in the region of first ionization potential (FIP) that defines the onset of elemental fractionation relative to the photospheric abundances. The photospheric abundances of these elements relative to low FIP elements (e.g., Fe, Mg) are presumably well known.**
- **Improved models of the FIP elemental fractionation are crucial to evaluating the magnitude of possible isotopic fractionations of the solar wind relative to the Sun.**

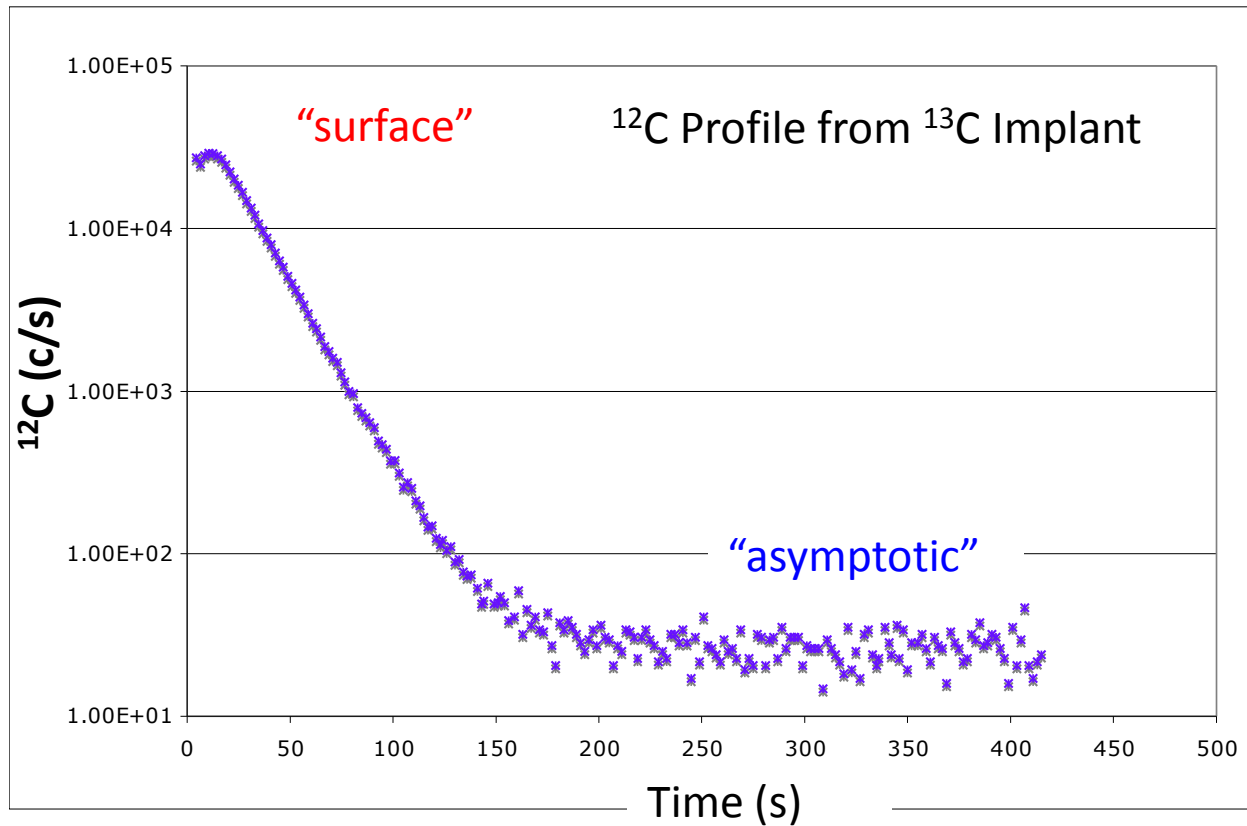


## Analyzing C & N with SIMS

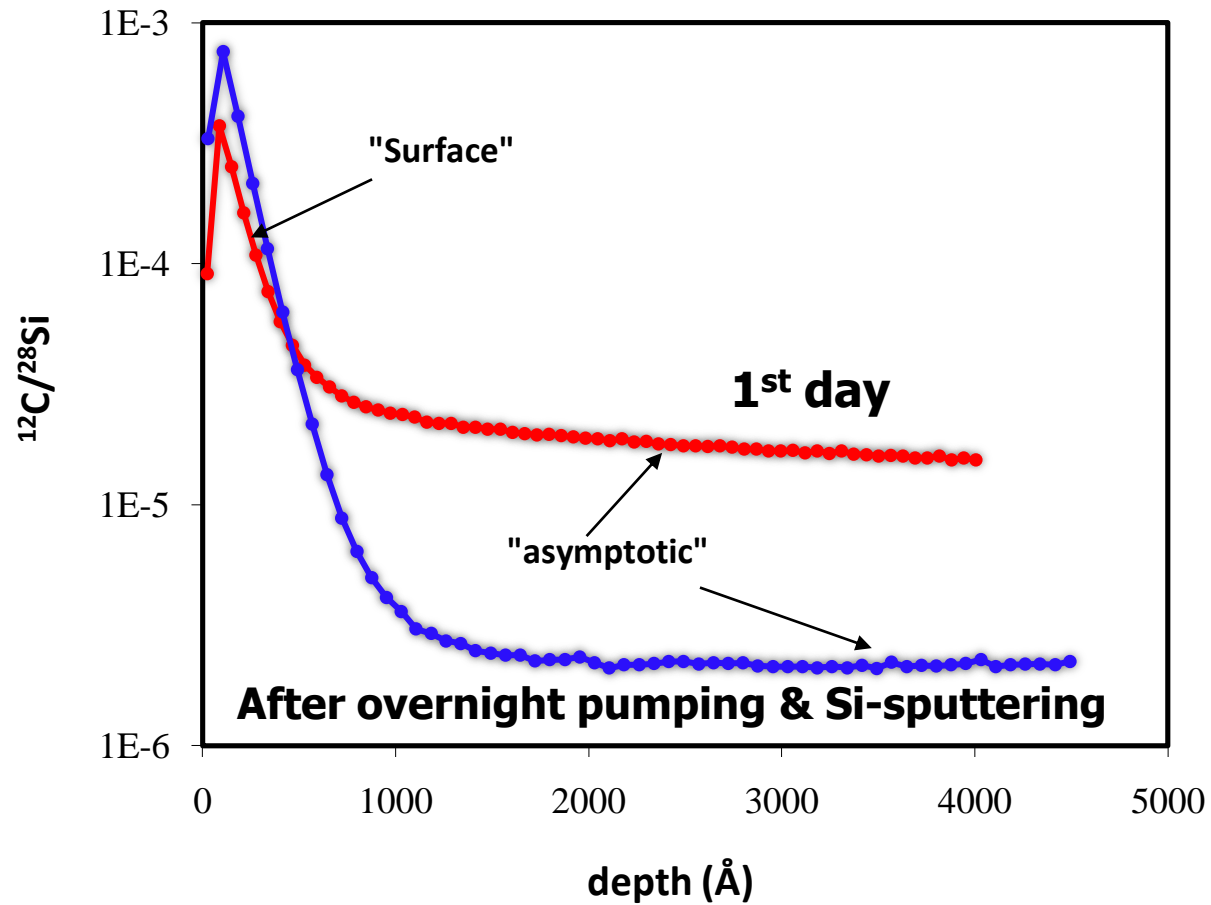
---

- **The sensitivity to measure C and N in Genesis samples by SIMS exists, but several attempts over the past couple of years have failed because of instrumental background and surface contamination.**
- **The best attempt to date on C and N with our new Cameca 7f-Geo.**
- **Combined FIB and NanoSIMS approach for “backside” profiling.**

# Two Sources of Background



# Reduce "Asymptotic" Background



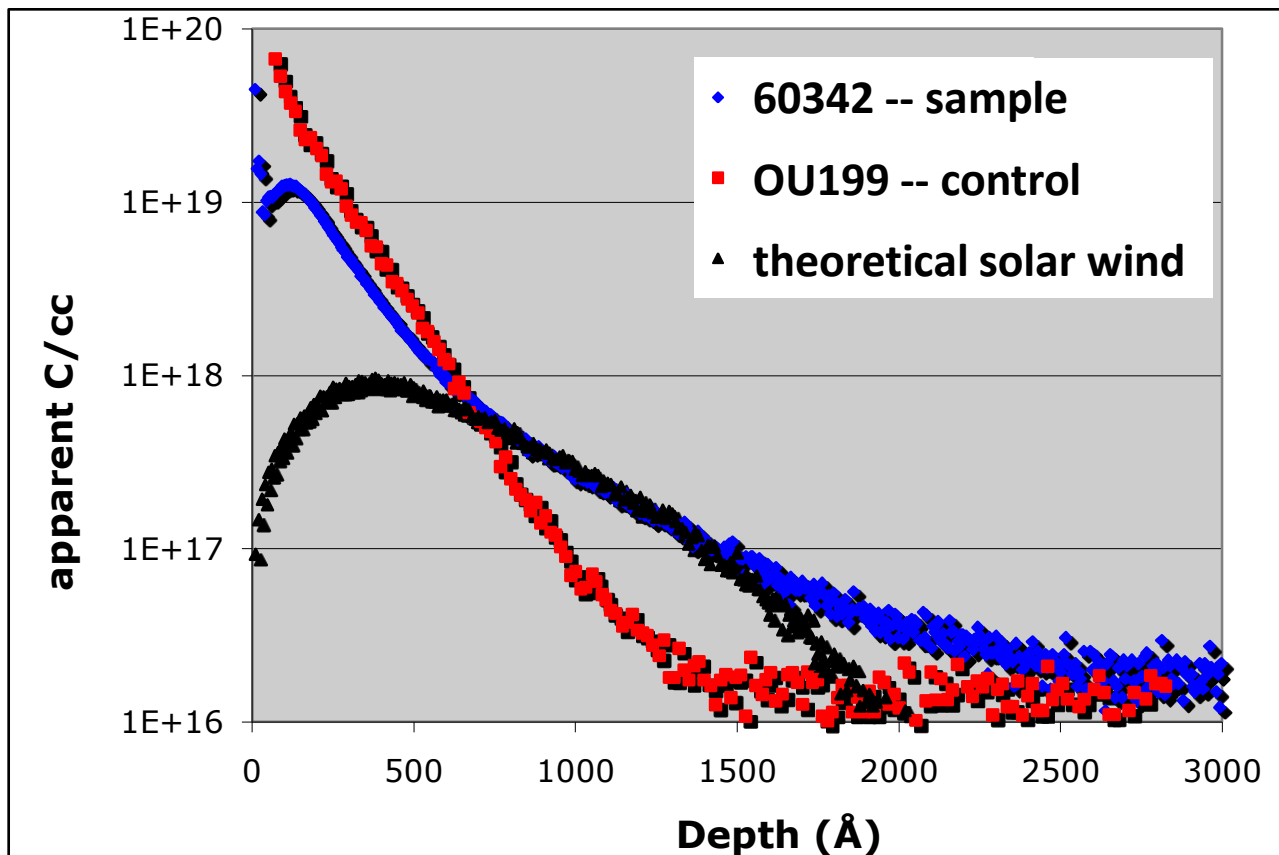


## Analytical Conditions – 7f Geo

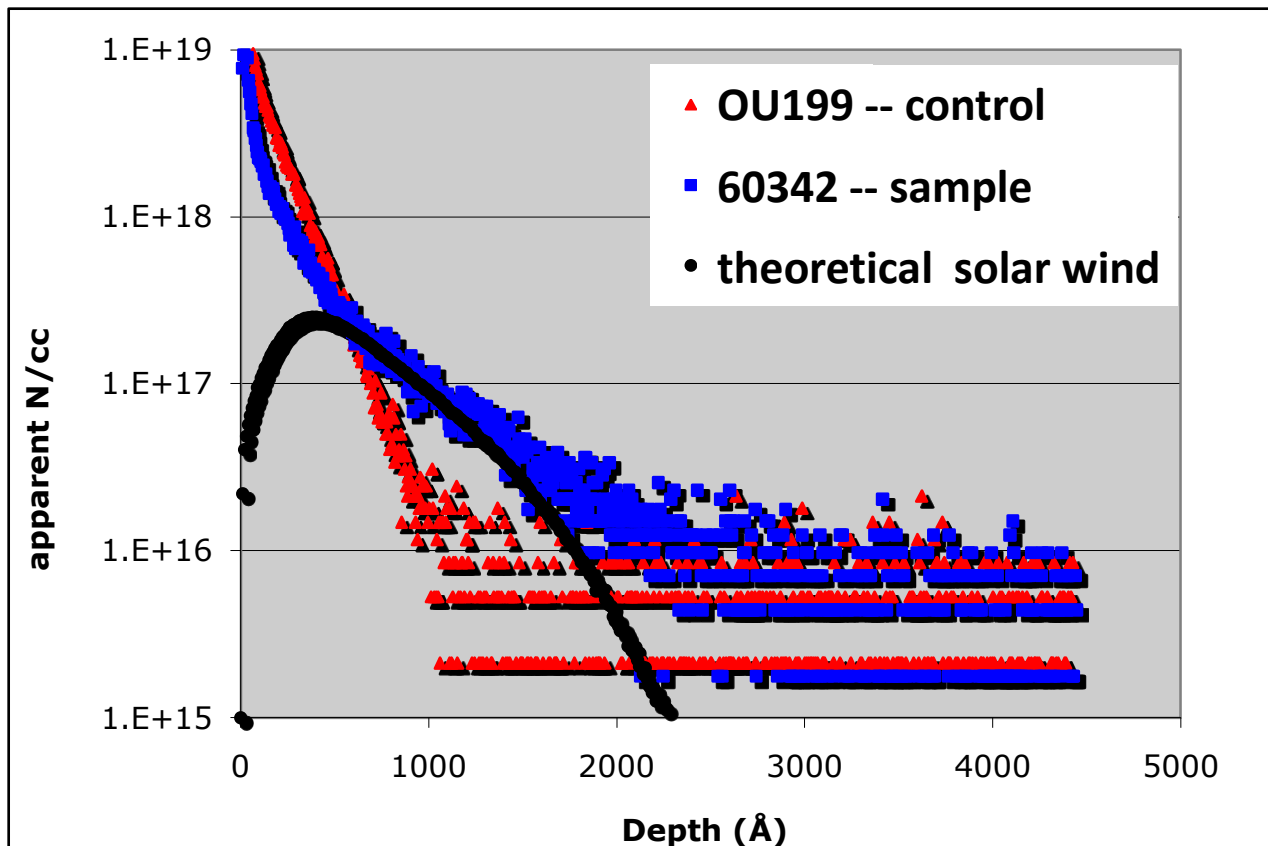
---

- **Primary beam: Cs+, 10 keV, ~9 nA**
- **Secondary HV: -5 or -10 keV**
- **MRP: ~6000 →  $^{29}\text{Si}^{13}\text{C}$ ;  $^{28}\text{Si}^{14}\text{N}$**
- **Field aperture: 50  $\mu\text{m}$**
- **Raster size: 100 micron**
- **Sputtering rate: ~ 5  $\text{\AA}/\text{sec}$**
- **Overnight sputtering Si**

# $^{12}\text{C}$ Profiles in Control & 60342

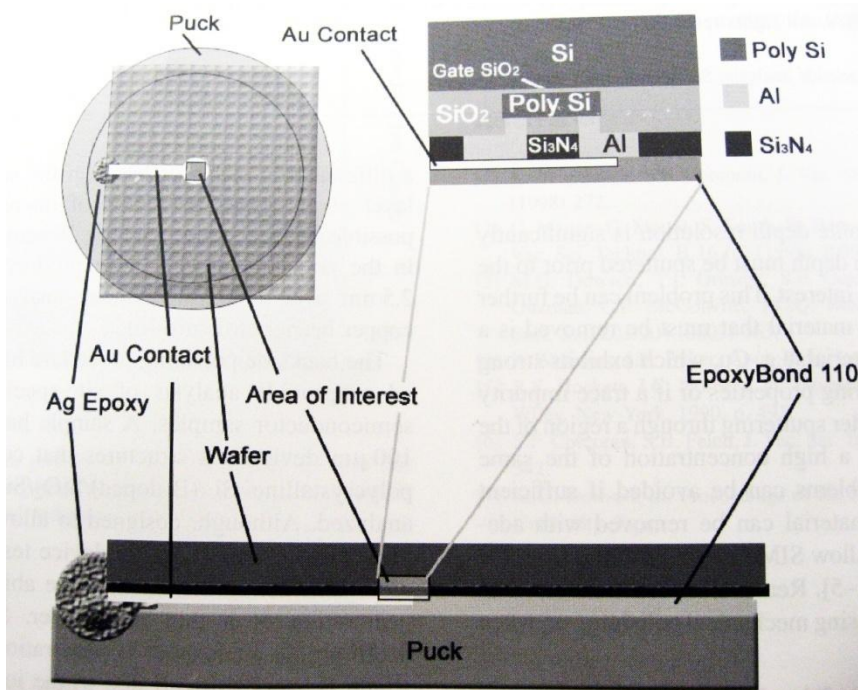


# $^{15}\text{N}$ Profiles in Control & 60342

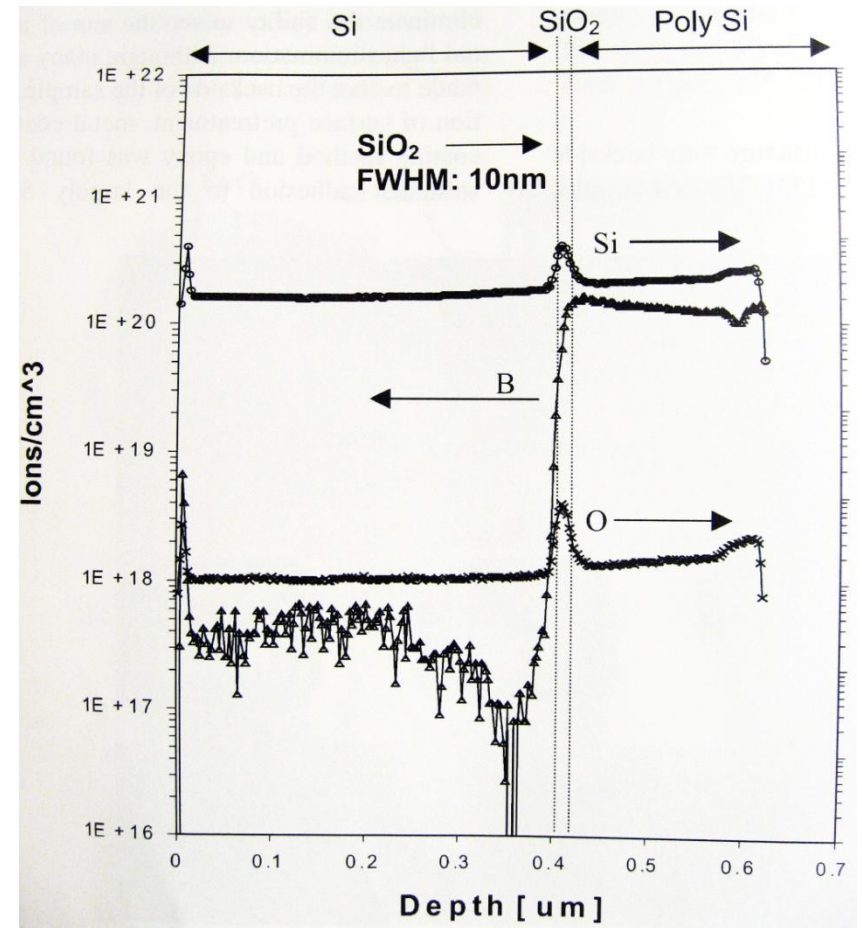




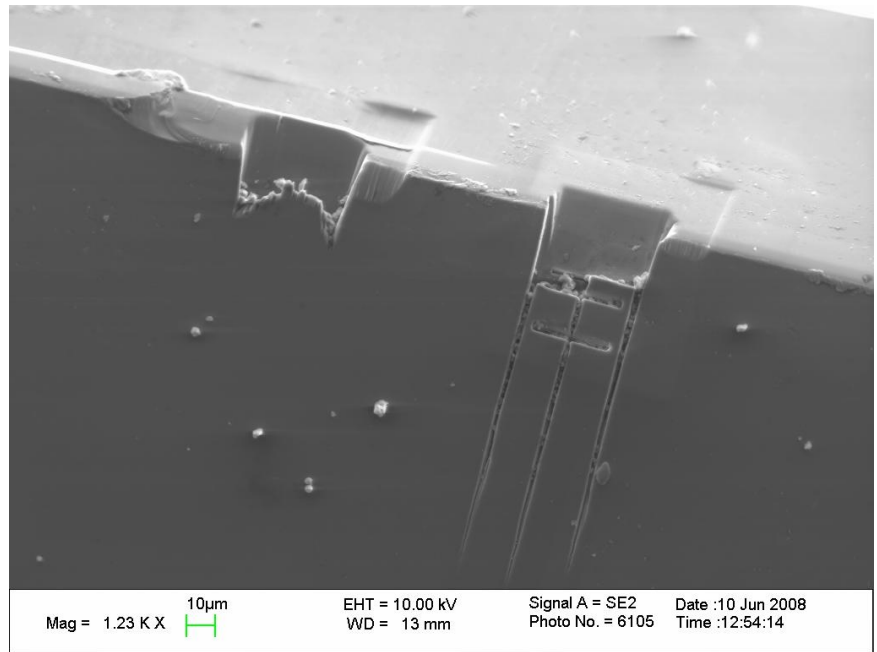
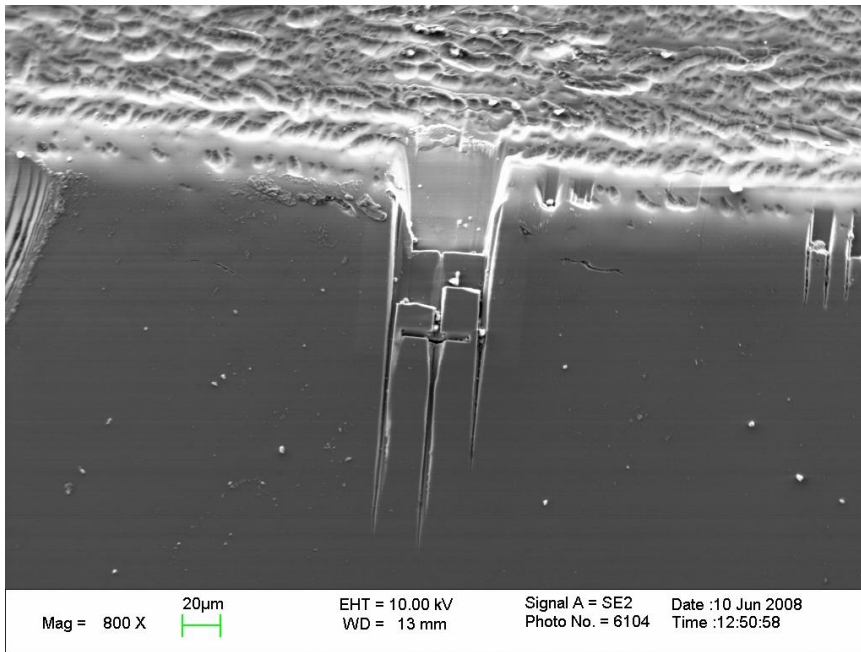
# Backside Profiling – Solution for Surface Contamination?



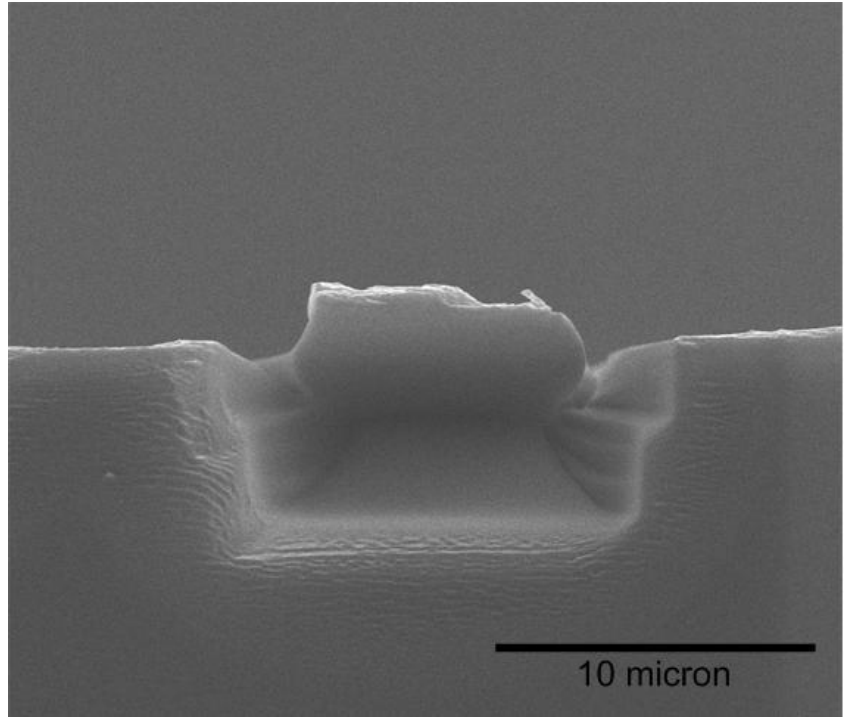
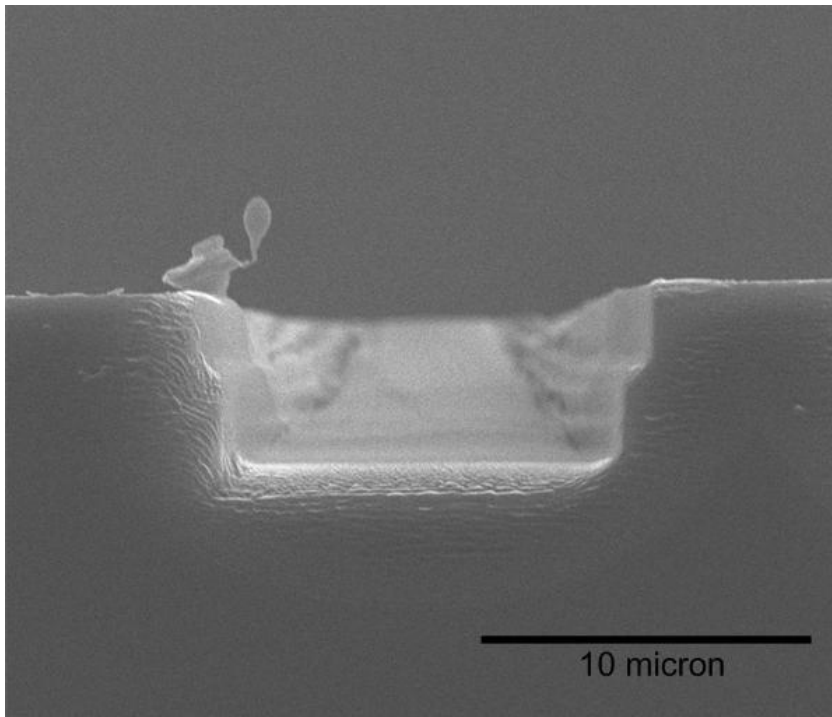
Gu et al. (2004)

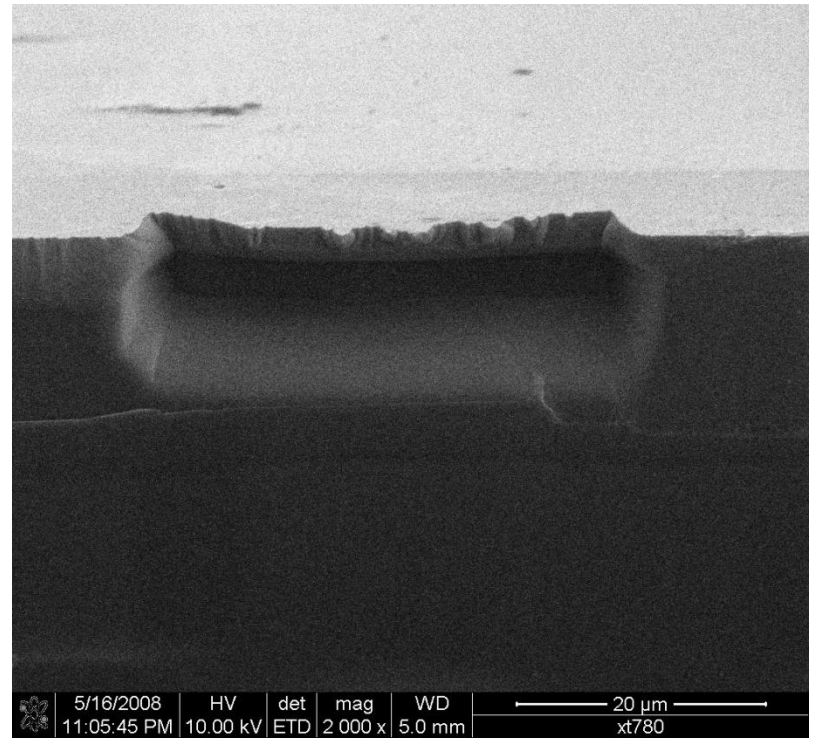
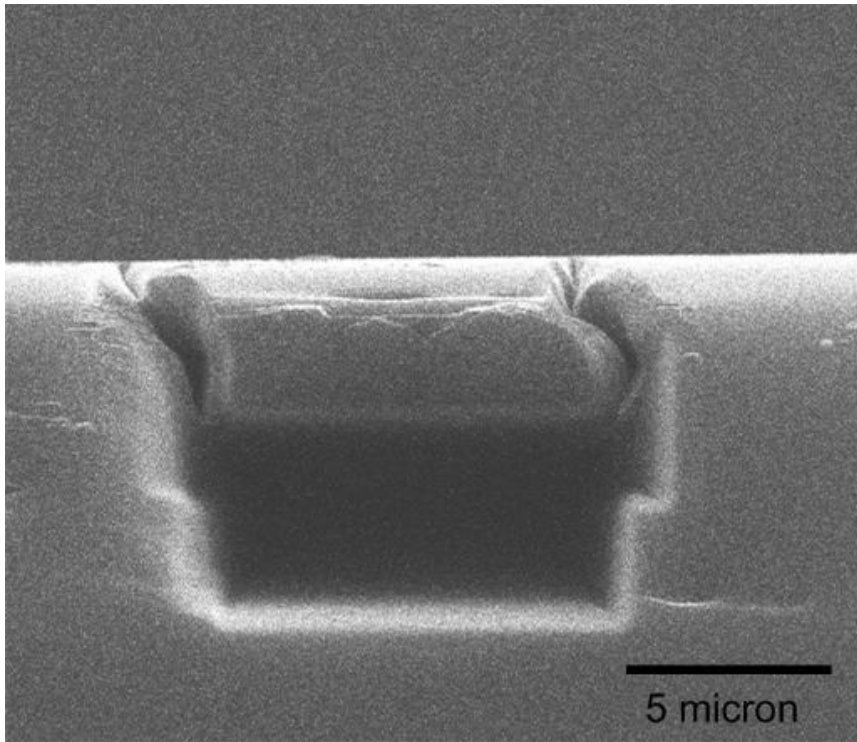


# “Micro-scale” backside profiling? --preparing samples for NanoSIMS with FIB

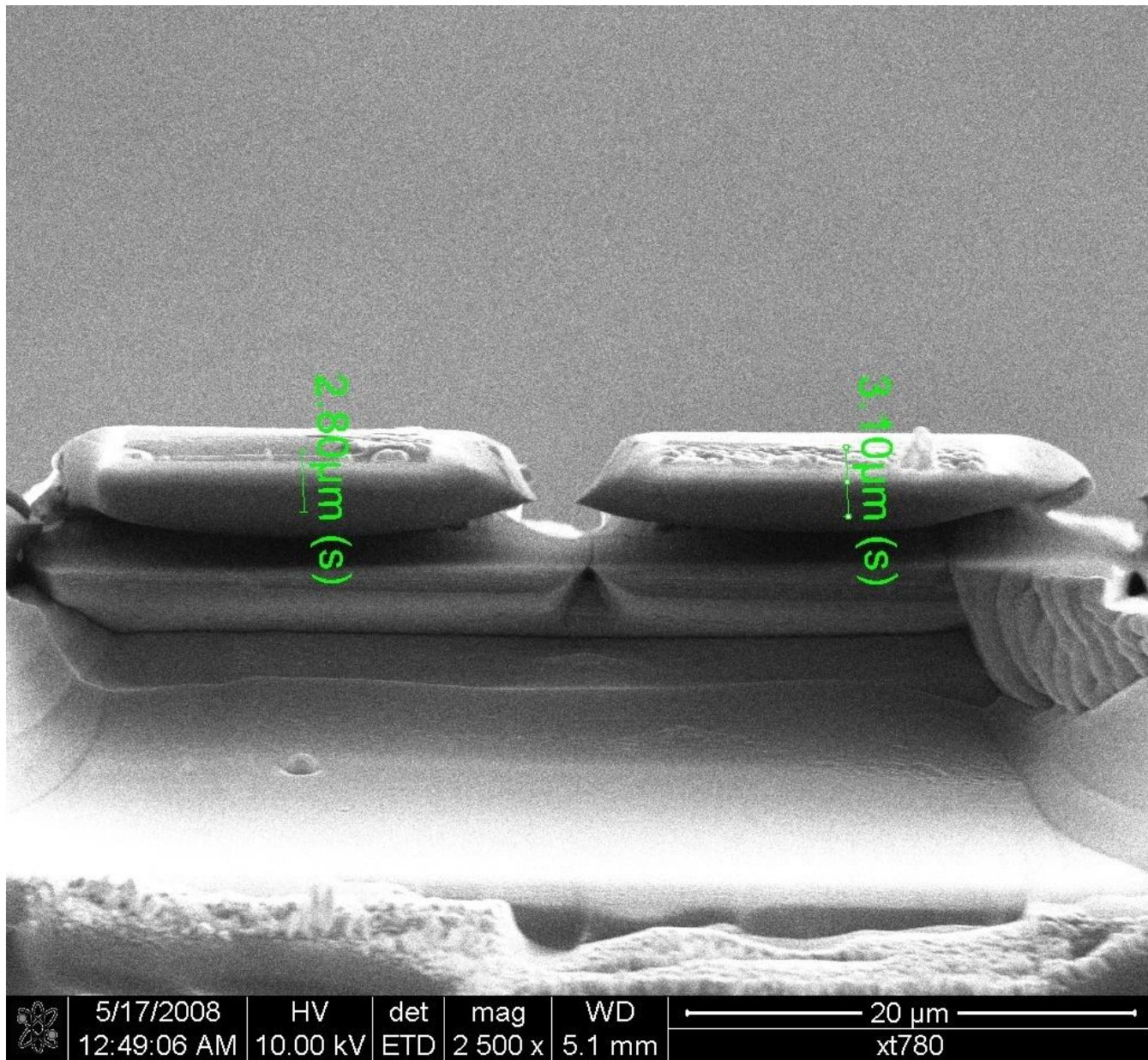


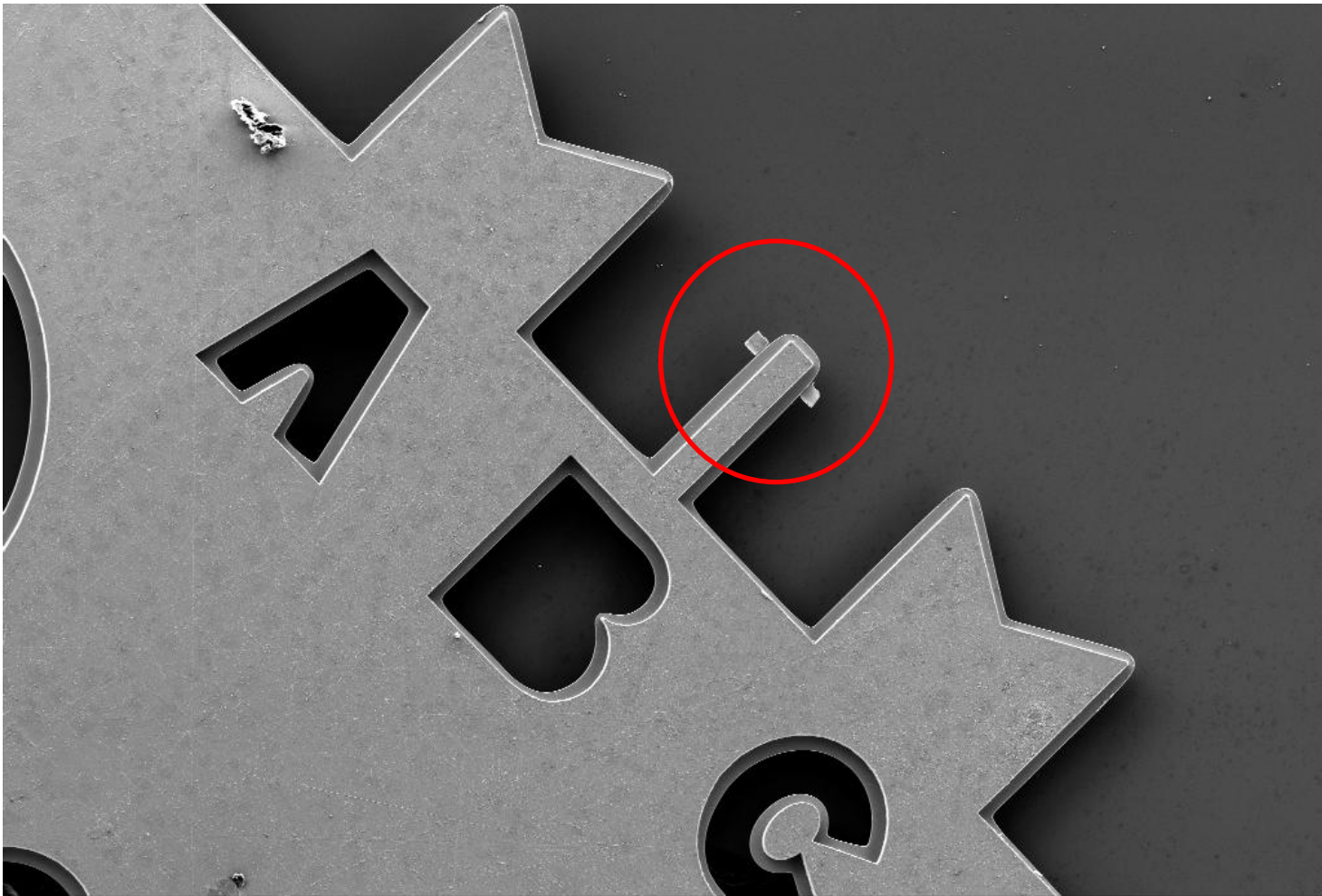
(SEM images from Caltech FIB)












Mag = 300 X

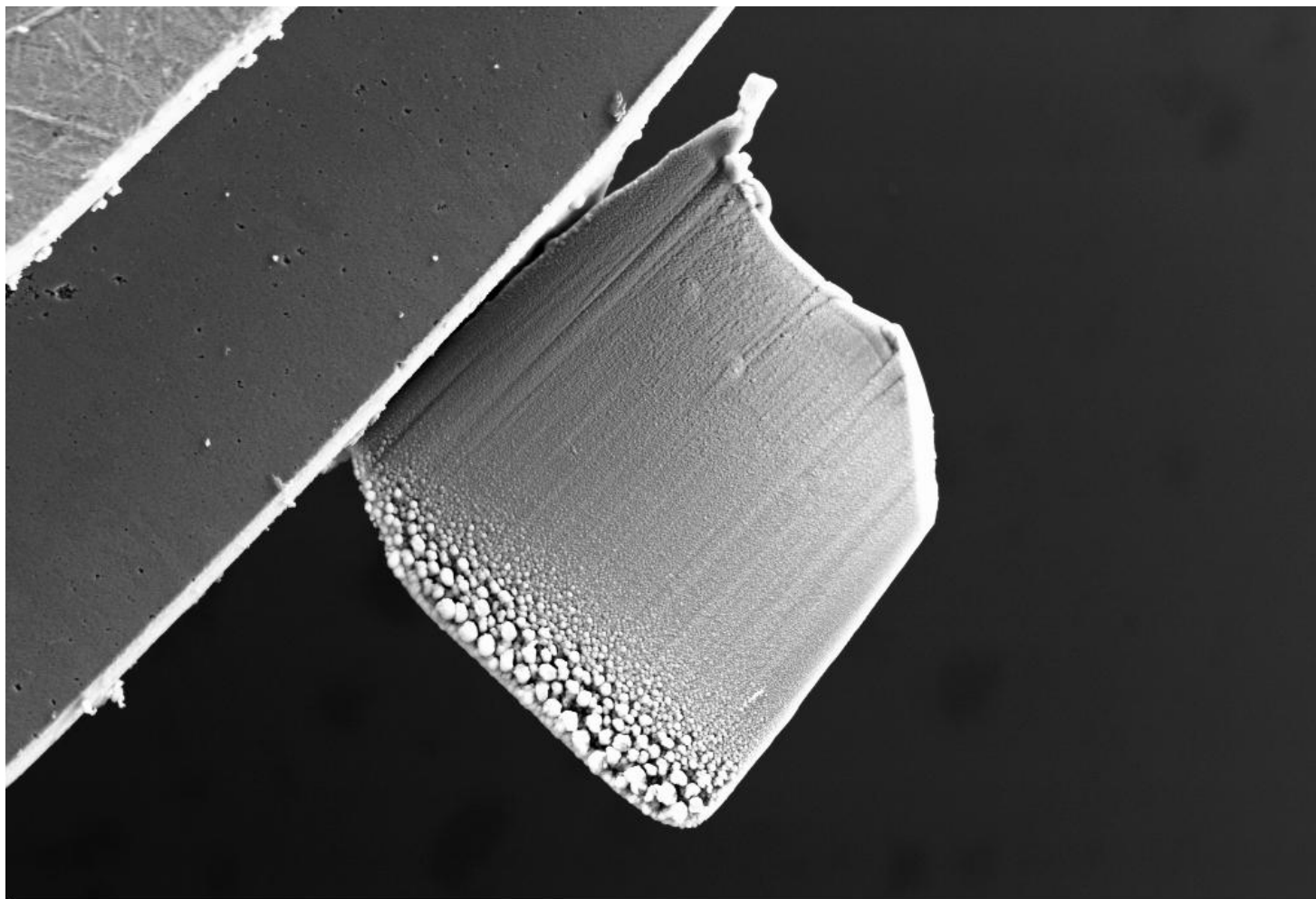
100µm  


EHT = 8.00 kV  
WD = 5 mm

Signal A = SE2  
Photo No. = 5783

Date :4 Jun 2008  
Time :9:37:48



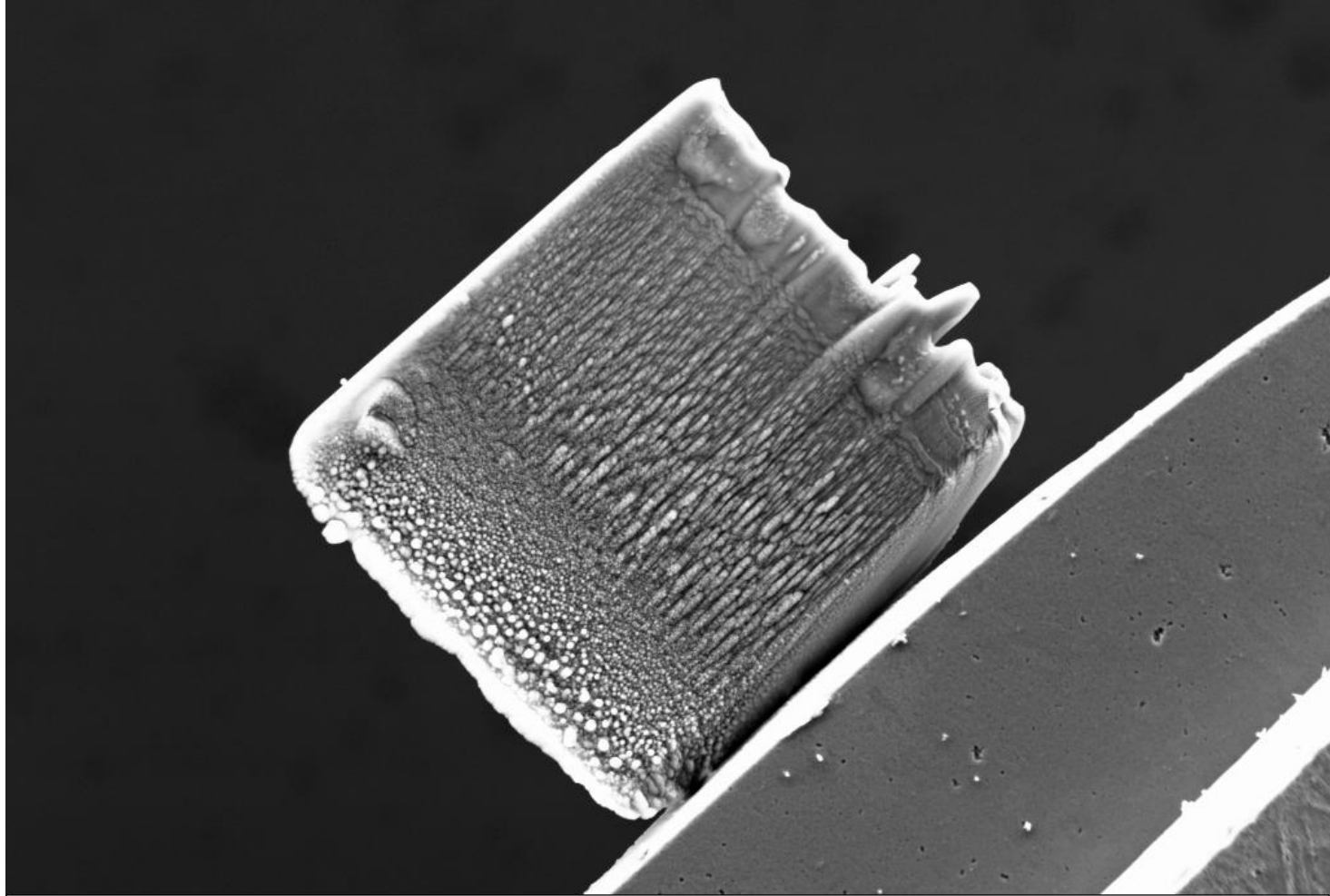


Mag = 9.00 K X    2µm  
|-----|

EHT = 8.00 kV  
WD = 5 mm

Signal A = SE2  
Photo No. = 5782

Date :4 Jun 2008  
Time :9:35:41



Mag = 9.00 K X    2 $\mu$ m  
|-----|

EHT = 8.00 kV  
WD = 5 mm

Signal A = SE2  
Photo No. = 5781

Date :4 Jun 2008  
Time :9:32:32



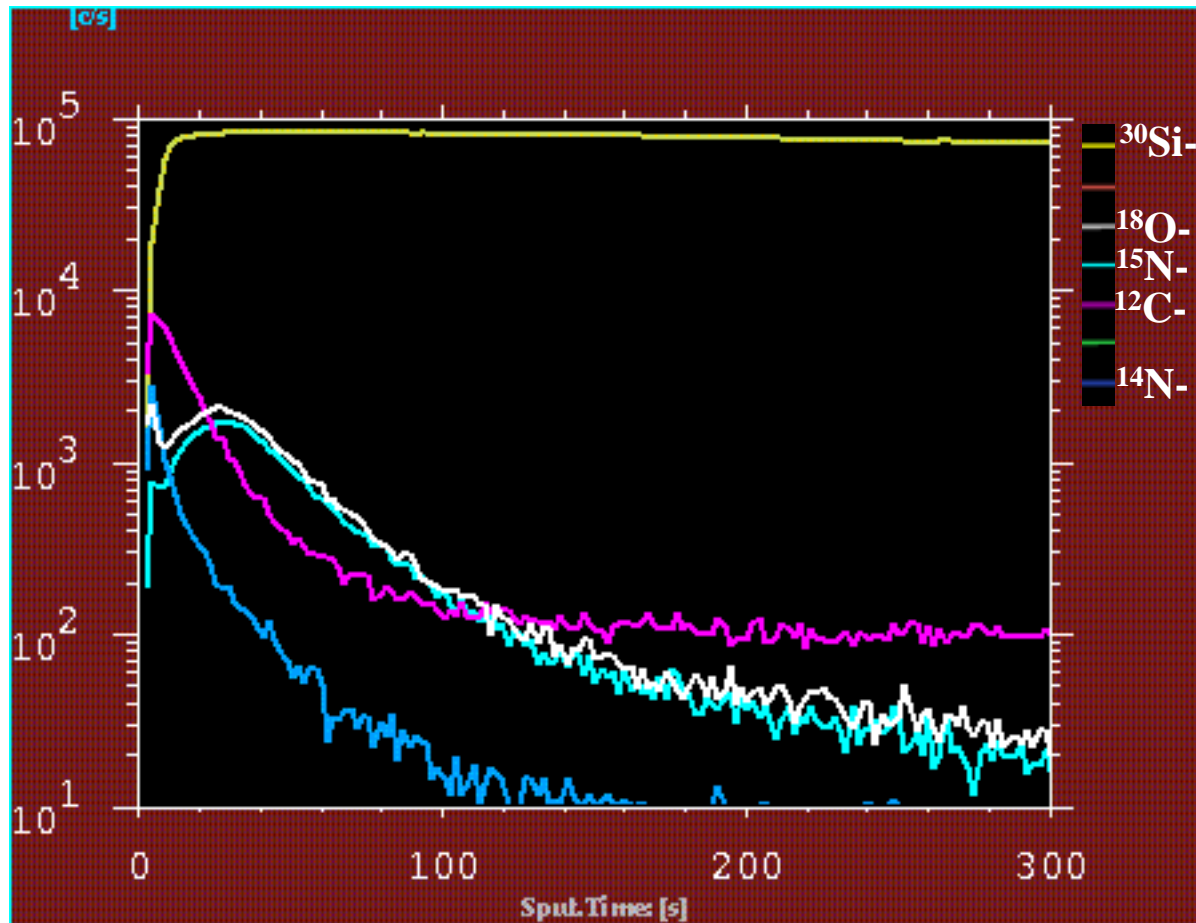


## Analytical Conditions – NanoSIMS 50L

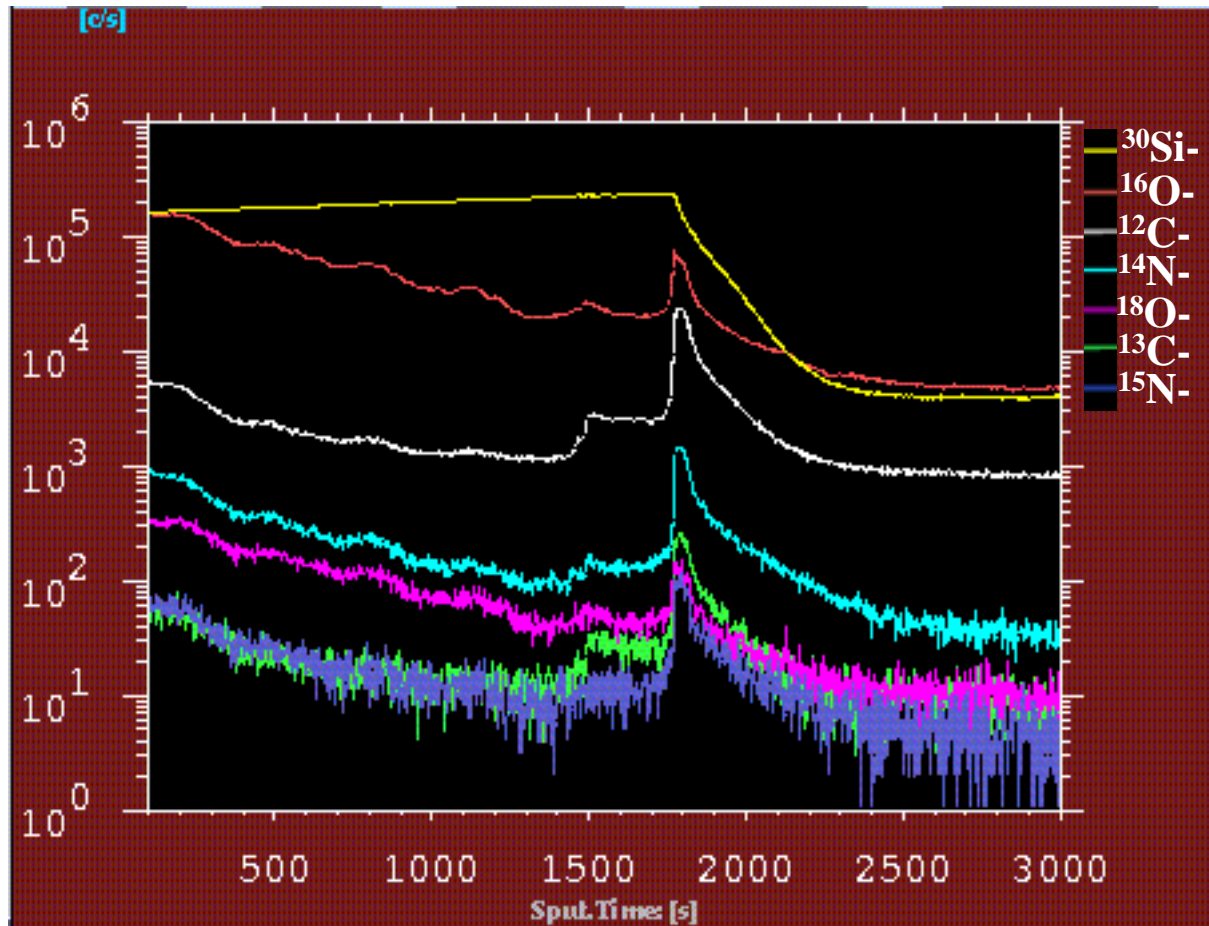
---

- 7 detectors set up for masses:  $^{12}\text{C}^-$ ,  $^{13}\text{C}^-$ ,  $^{16}\text{O}^-$ ,  $^{18}\text{O}^-$ ,  $^{28}\text{Si}^-$ ,  $^{14}\text{N}^{28}\text{Si}^-$ , and  $^{15}\text{N}^{28}\text{Si}^-$
- Cs<sup>+</sup> beam current on samples (FCo): ~ 15 – 30 pA
- Raster size: 3x3 μm (2x2 μm gating)
- Sputtering rate: ~4 -- 8 Å/sec

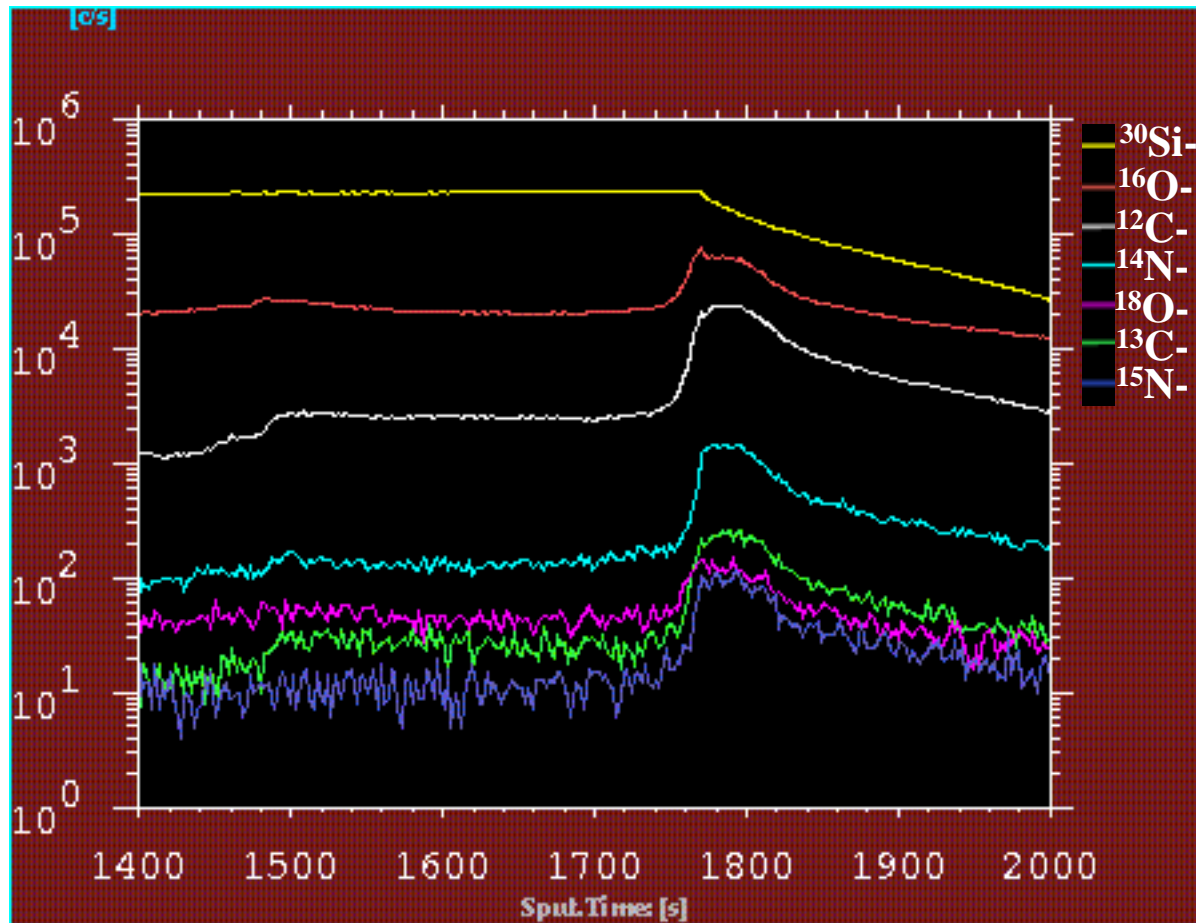
# Profiles of an $^{15}\text{N}$ & $^{18}\text{O}$ Implant– HRL99, 9



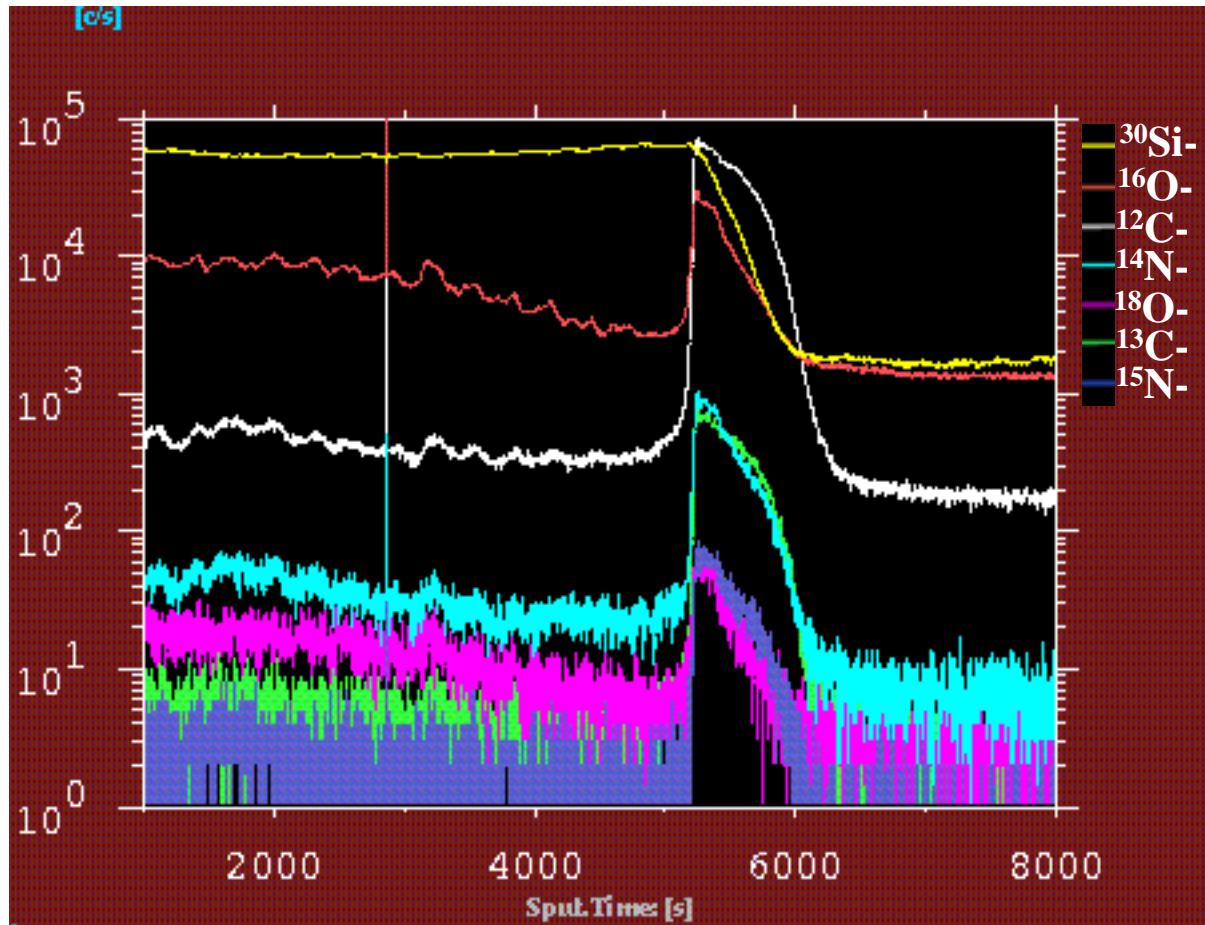
# Spot-1 on the FIB Cut-out of $^{13}\text{C}$ Implant



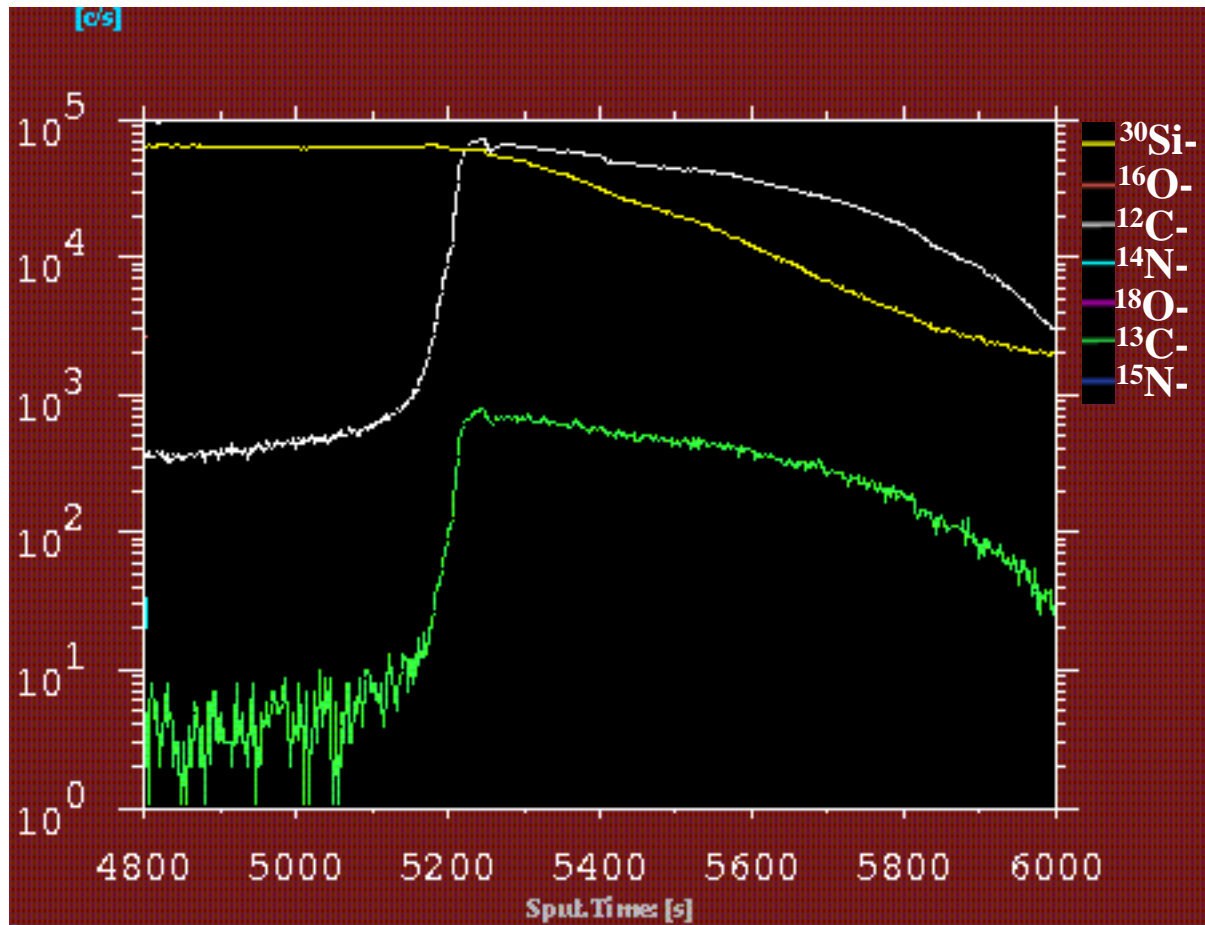
# Spot-1 on the FIB Cut-out of $^{13}\text{C}$ Implant



# Spot-4 on the FIB Cut-out of $^{13}\text{C}$ Implant

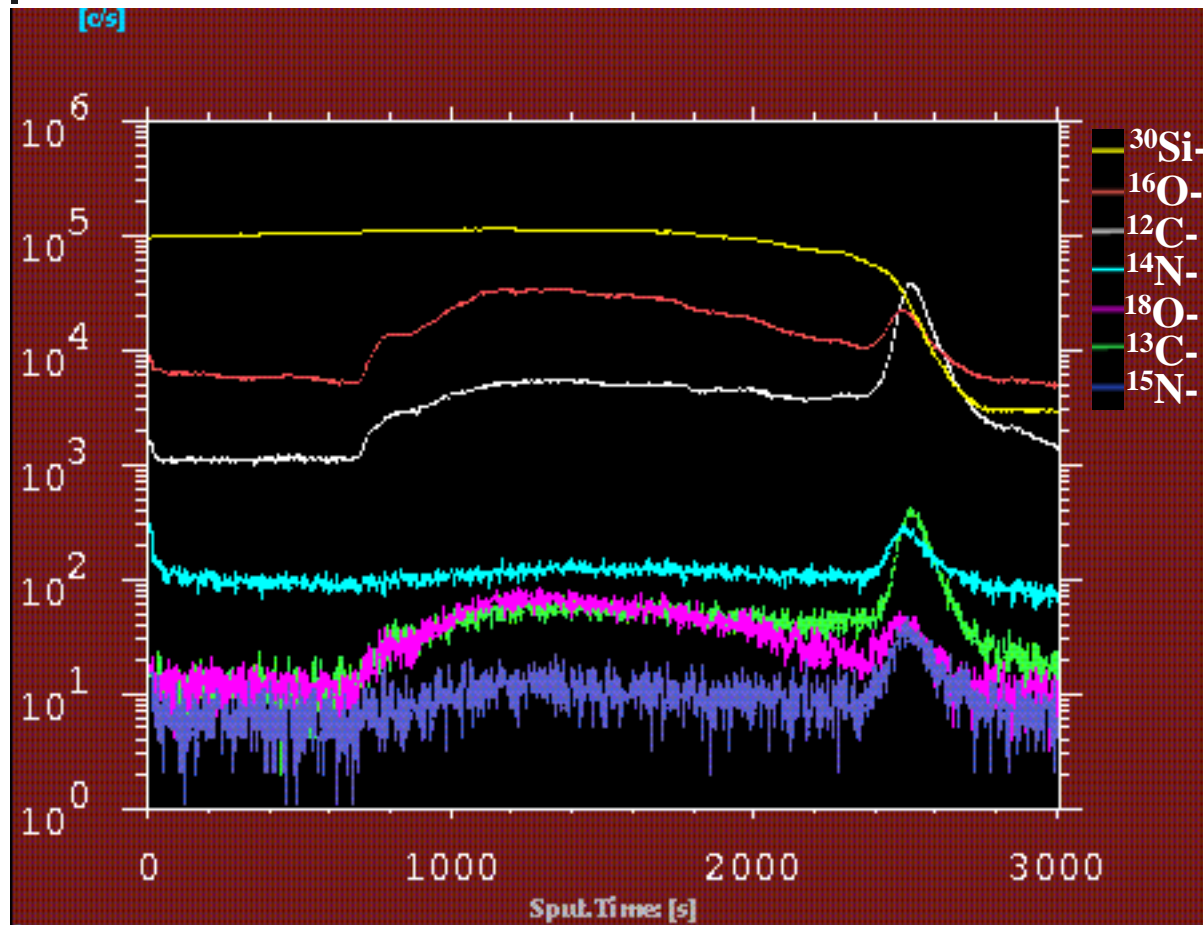


# Spot-4 on the FIB Cut-out of $^{13}\text{C}$ Implant



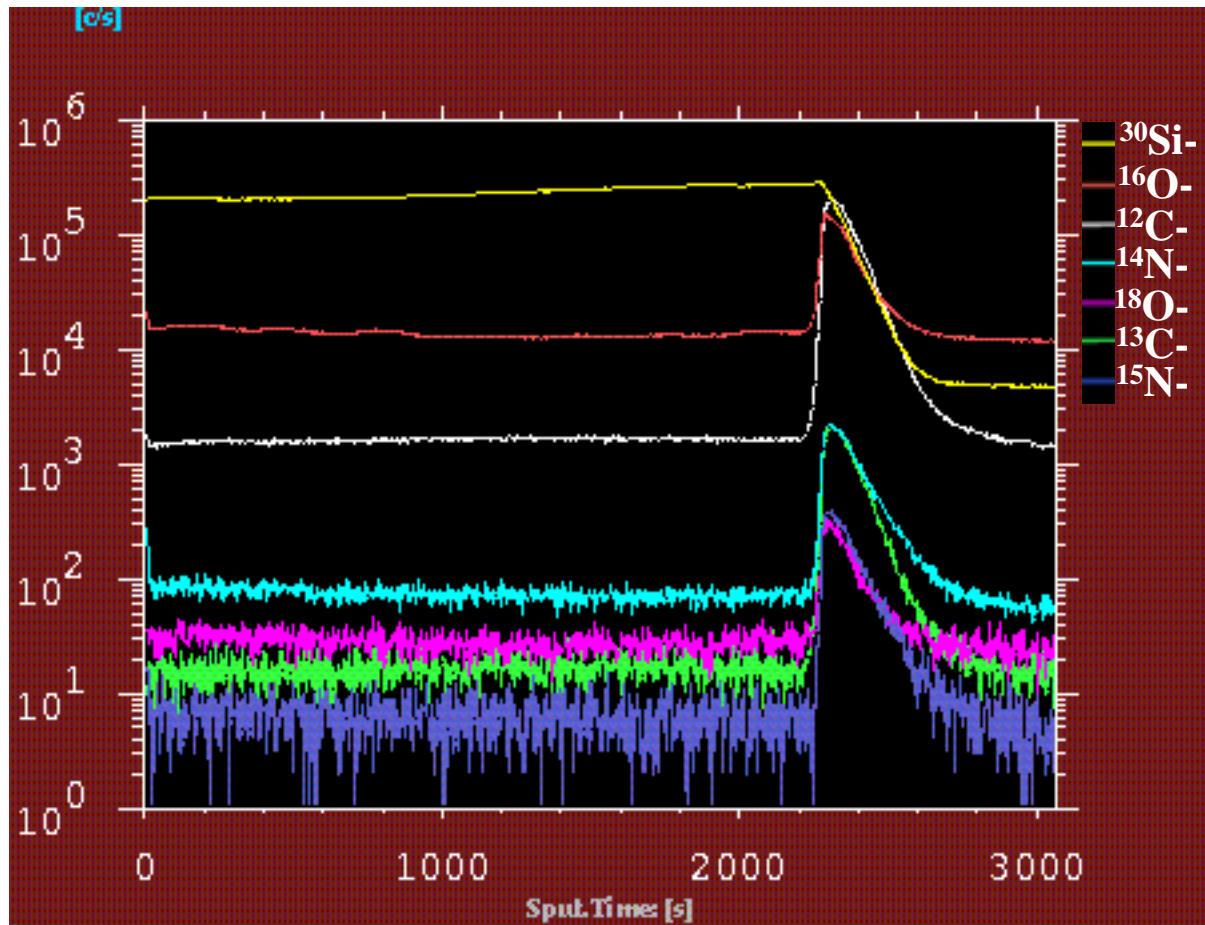


# Spot-1 on the FIB Cut-out of Flight Sample 60342



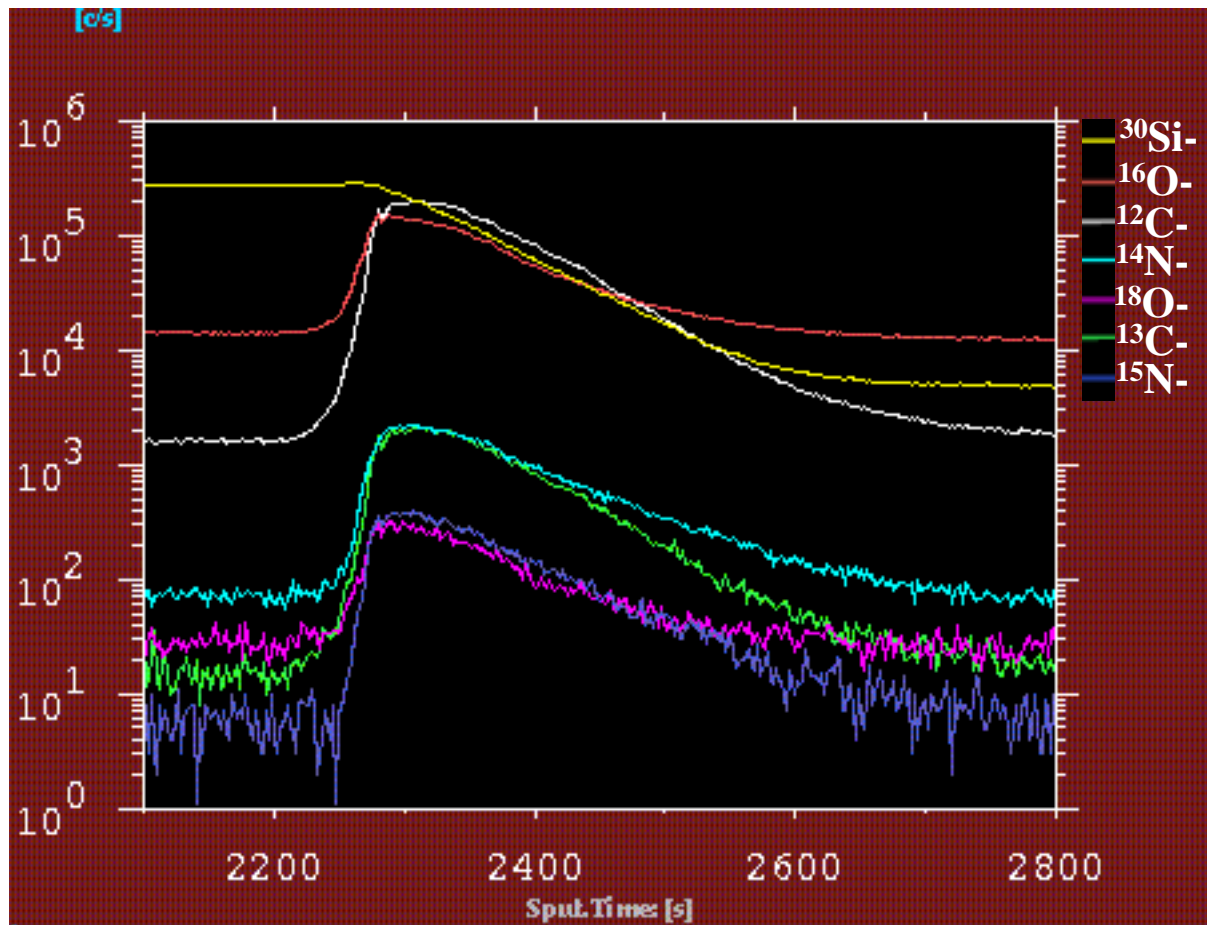
**contamination?**

# Spot-2 on the FIB Cut-out of Flight Sample 60342



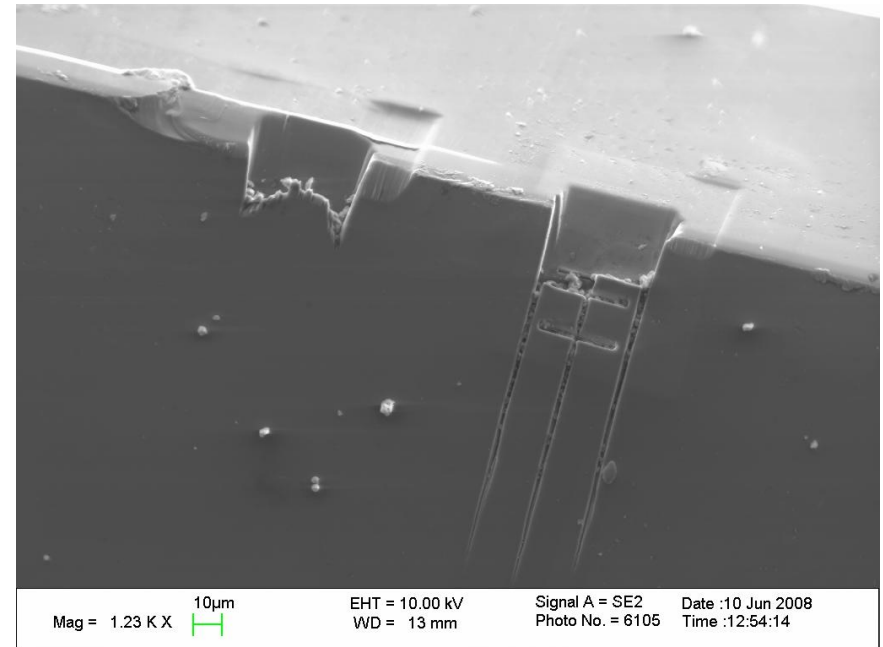
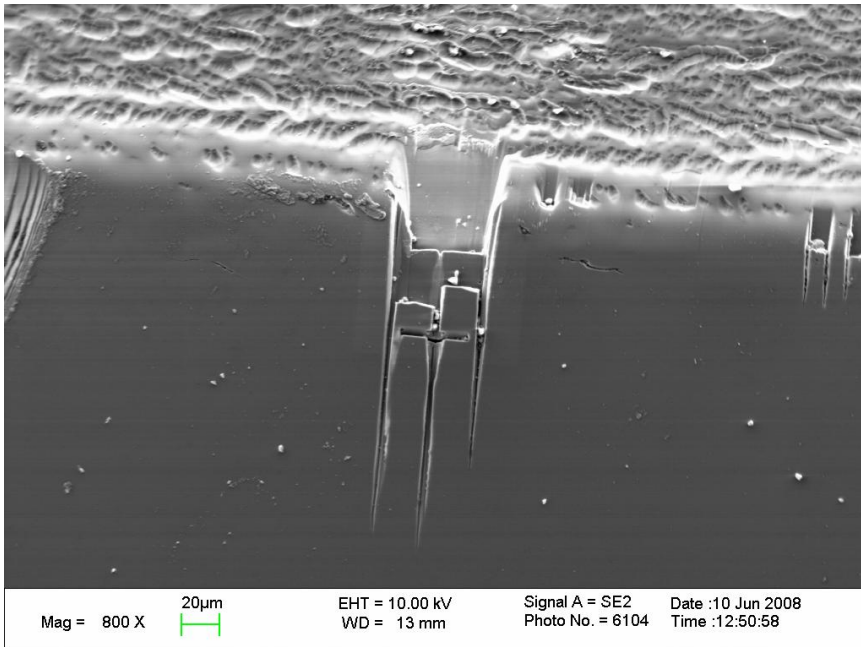


# Spot-2 on the FIB Cut-out of Flight Sample 60342



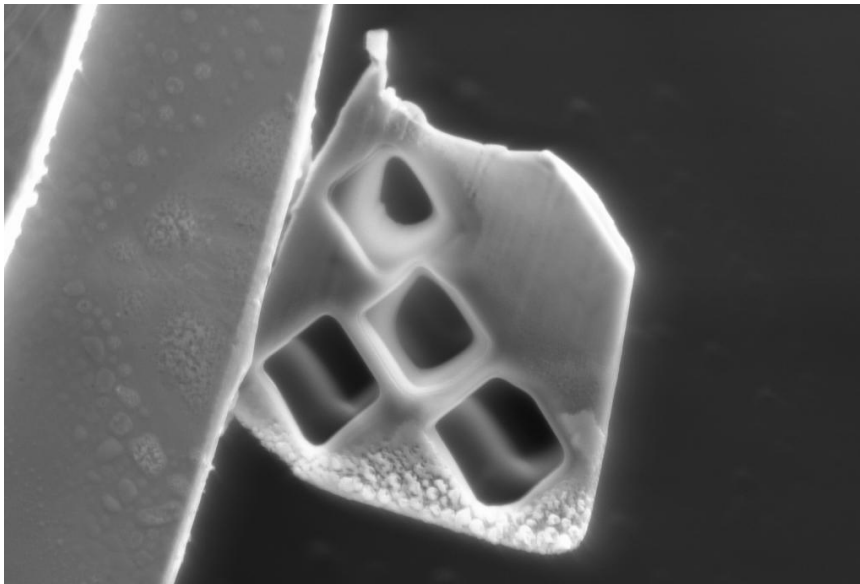
# Possible Causes for No Implant Profiles

- FIB “grazes” away the top layer of the  $^{13}\text{C}$  implant
- No  $^{13}\text{C}$  implant along the edge being cut out.

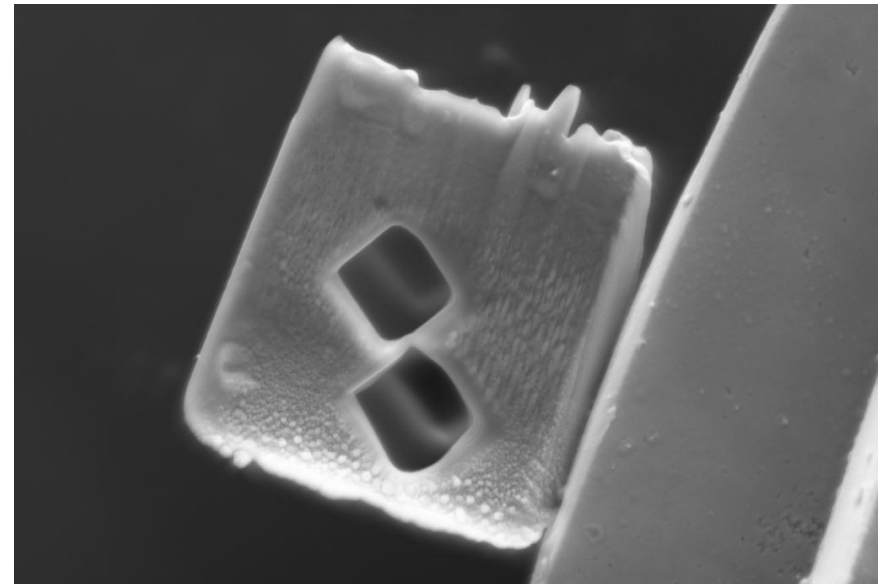


# More Possible Causes for No Implant Profiles

- Backsides of the FIB cut-outs are not parallel to the sample surfaces
- FIB cut-outs are not mounted parallel to the substrate surface.



Mag = 10.00 K X    2µm    EHT = 10.00 kV    Signal A = SE2    Date :10 Jun 2008  
WD = 12 mm    Photo No. = 6107    Time :13:01:27



Mag = 10.00 K X    2µm    EHT = 10.00 kV    Signal A = SE2    Date :10 Jun 2008  
WD = 12 mm    Photo No. = 6106    Time :12:58:11



## Summary

---

- **Low "asymptotic" background can be achieved in SIMS instruments for C and N. However, an apparent surface contamination component makes SIMS analysis of C and N fluences in Genesis samples extremely difficult, despite serious attempts to clean the samples.**
- **Our best profiling attempt to date indicate the presence of solar wind C and N in Genesis samples, though no quantification can be made.**
- **Backside profiling of Genesis samples with combined FIB and NanoSIMS techniques could provide a new approach for measuring C and N fluences of solar wind.**